

DRAWINGS (Draft)

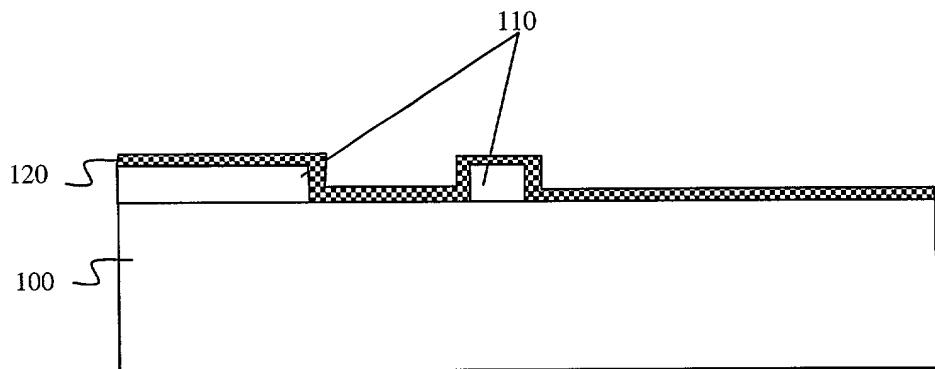


FIGURE 1a

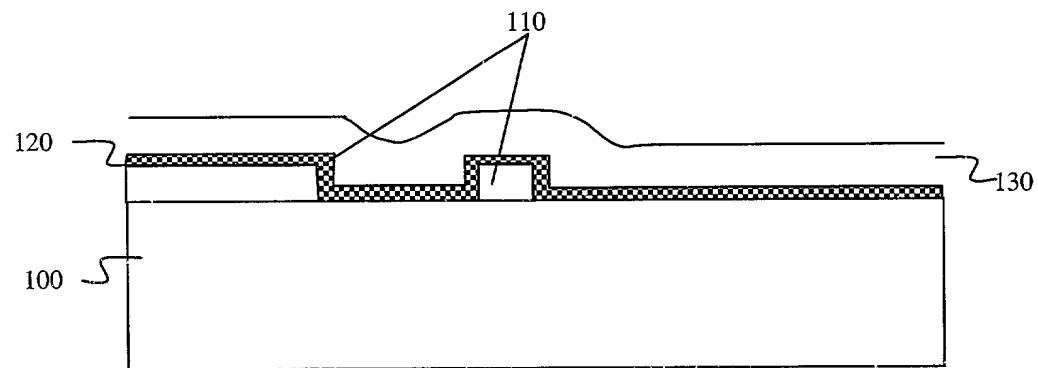


FIGURE 1b

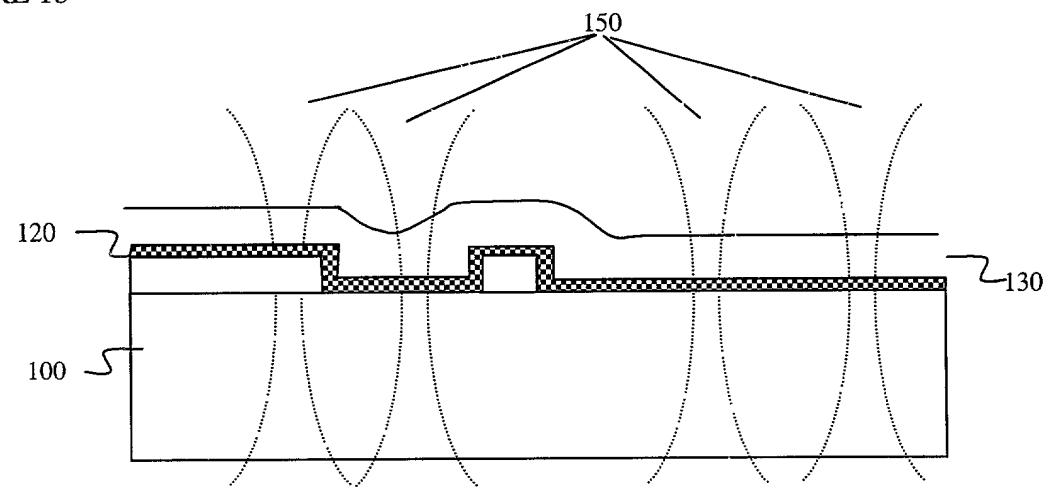


FIGURE 1c

Figure 1: Prior Art Lithography Processing

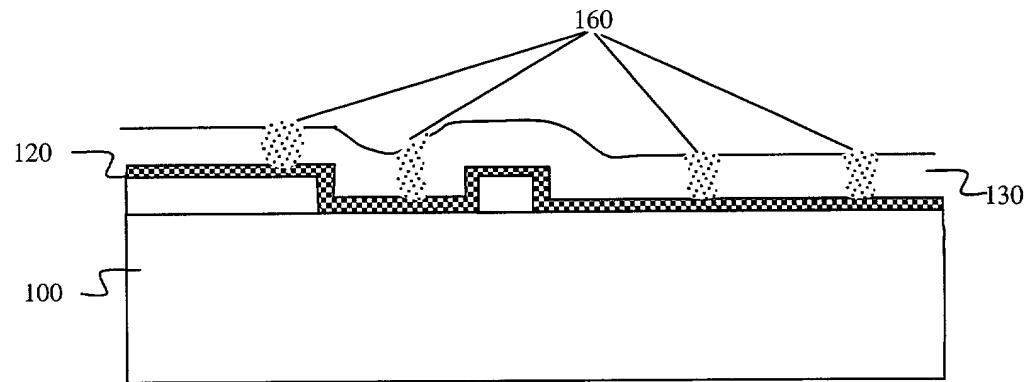


FIGURE 1d

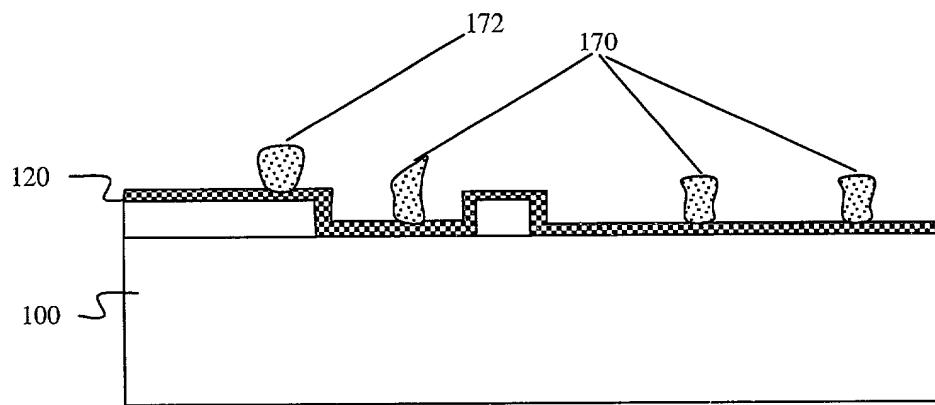


FIGURE 1e

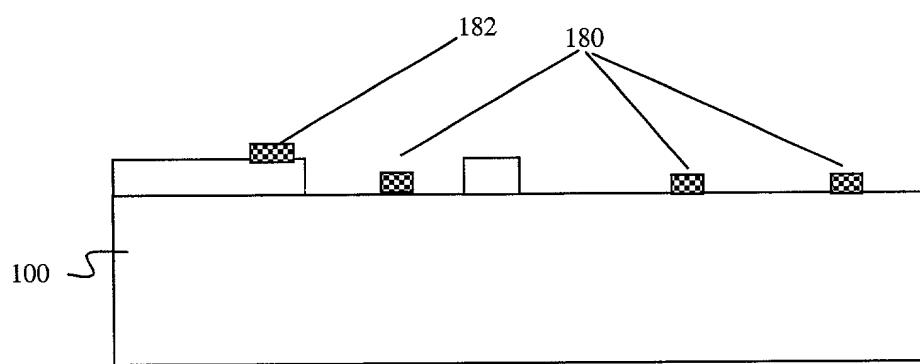


FIGURE 1f

Figure 1: Prior Art Lithography Processing

DRAWINGS (Draft)

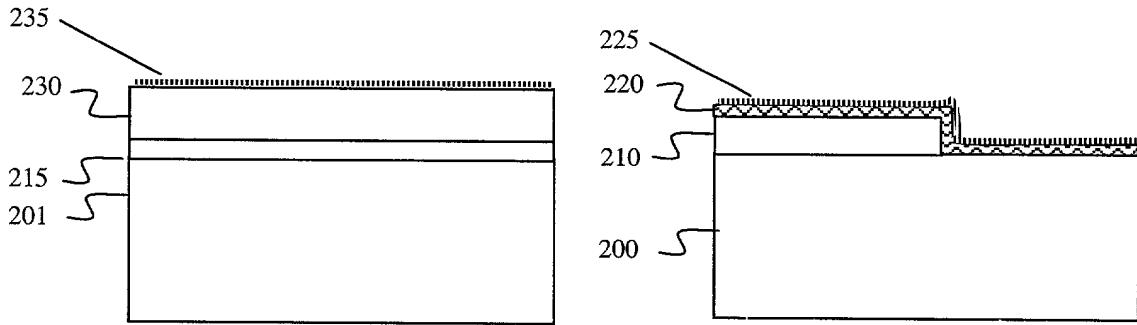


FIGURE 2a

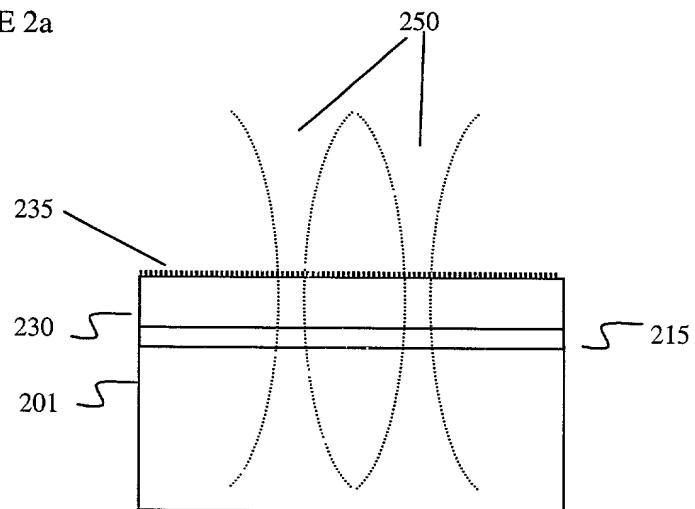


FIGURE 2b

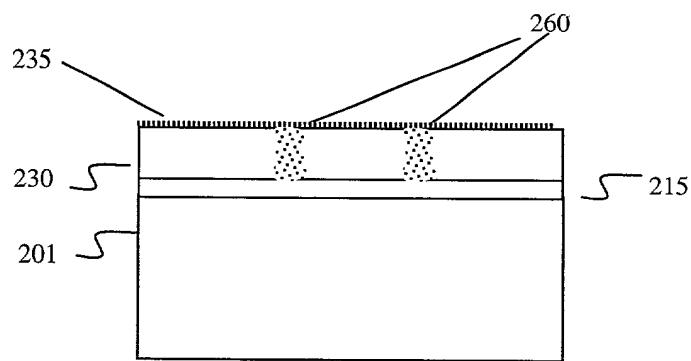


FIGURE 2c

DRAWINGS (Draft)

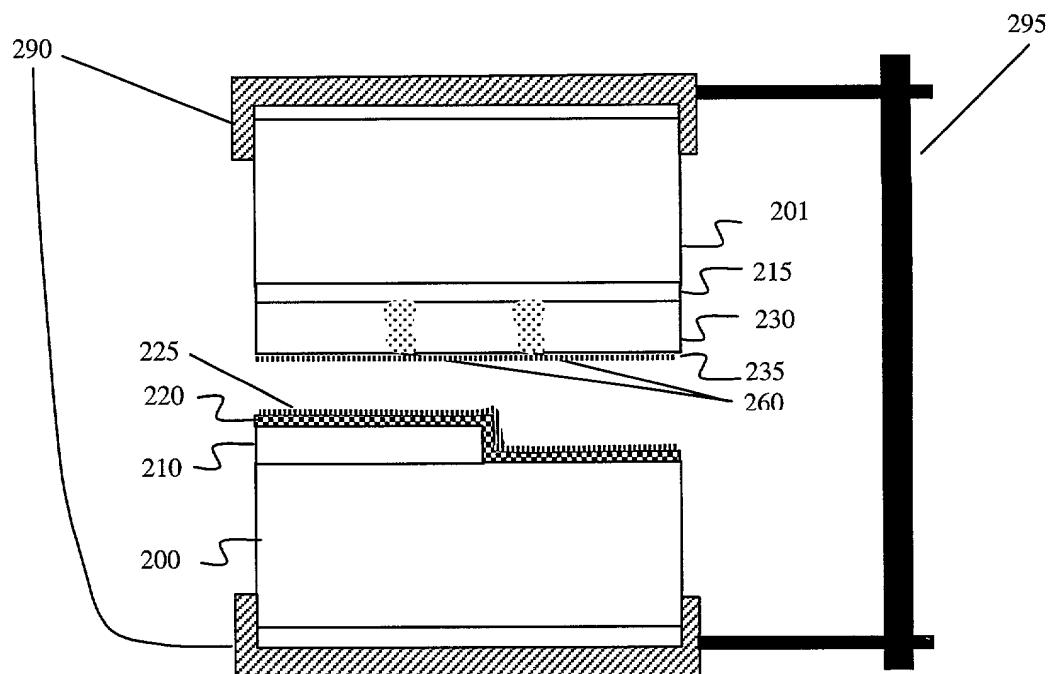


FIGURE 3a

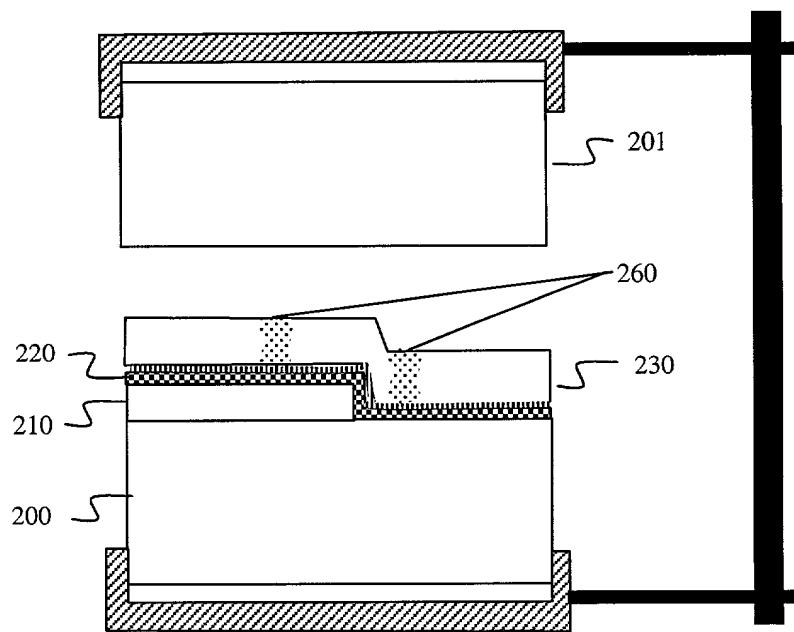


FIGURE 3b

DRAWINGS (Draft)

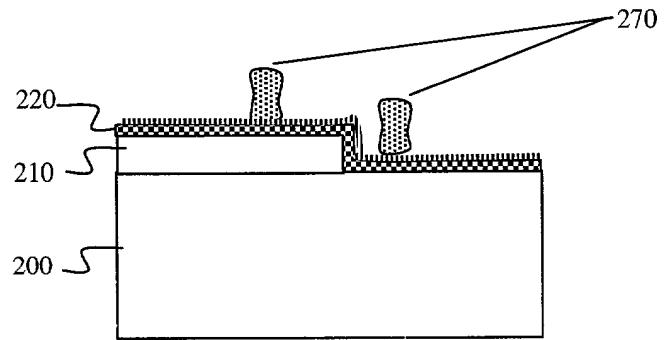


FIGURE 3c

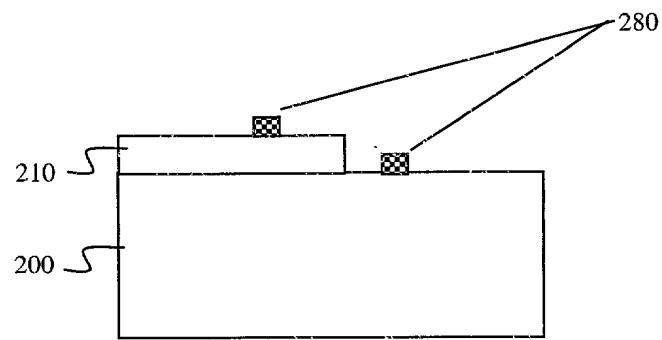


FIGURE 3d

DRAWINGS (Draft)

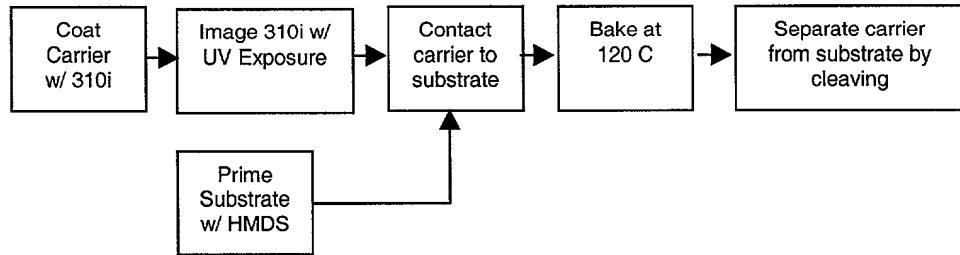


Figure 4a

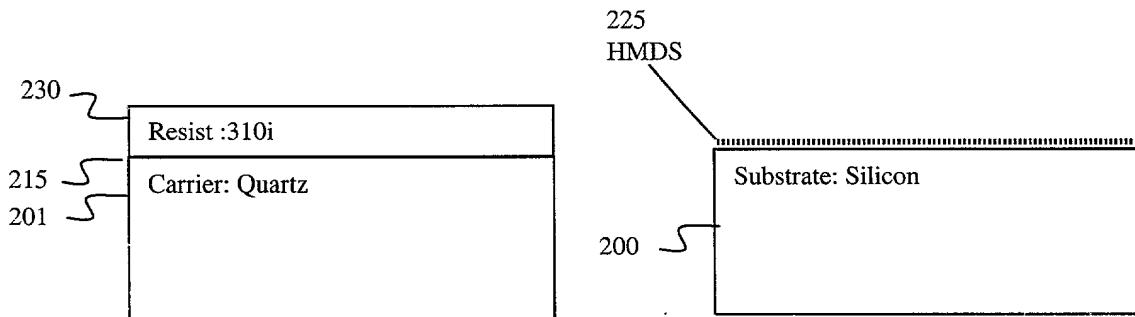


Figure 4b

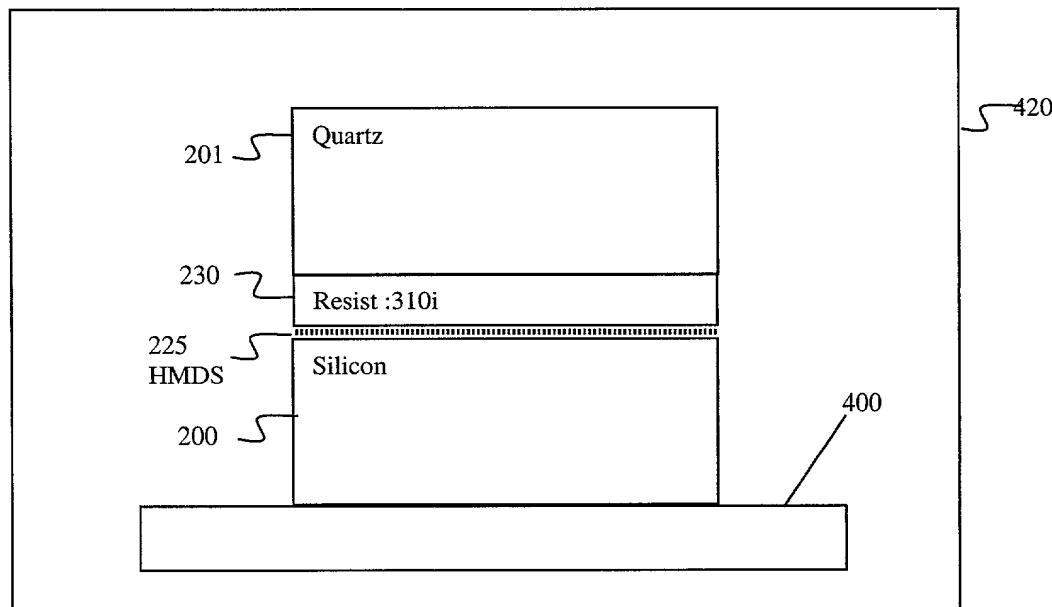


Figure 4c

DRAWINGS (Draft)

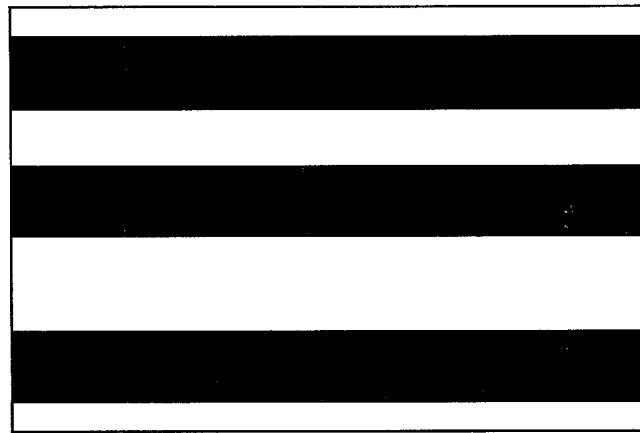


FIGURE 5: Mask Photo

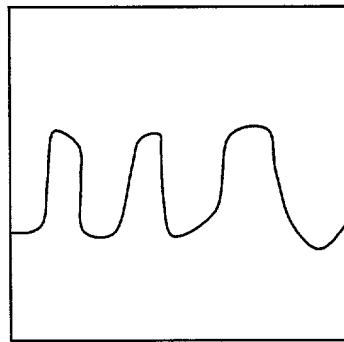


FIGURE 6a: Fringes before transfer

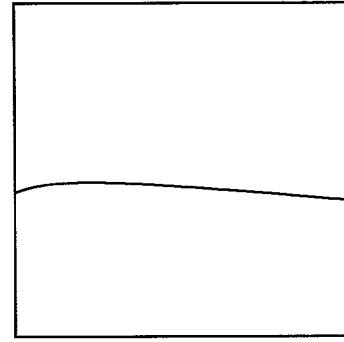


FIGURE 6b: Fringes after transfer

DRAWINGS (Draft)

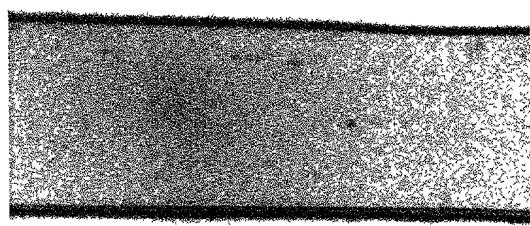


FIGURE 7: Developed Photoresist

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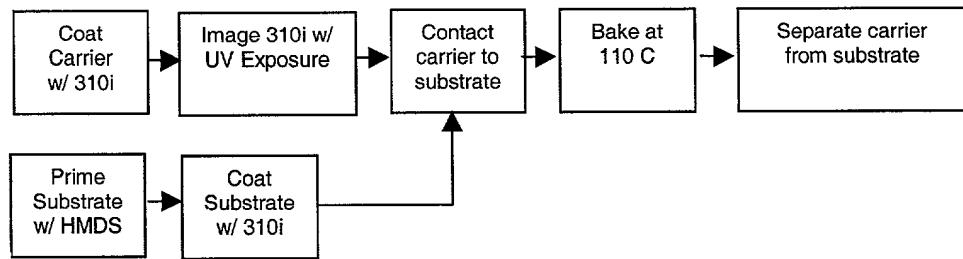


Figure 8a

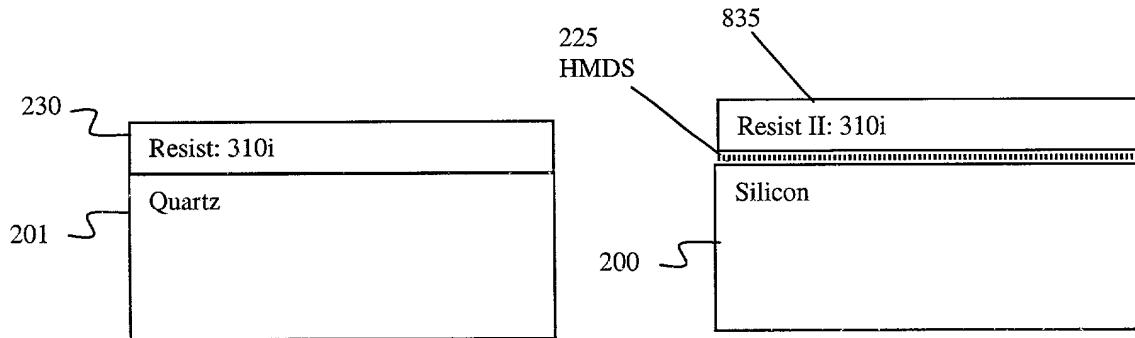


Figure 8b.

DRAWINGS (Draft)

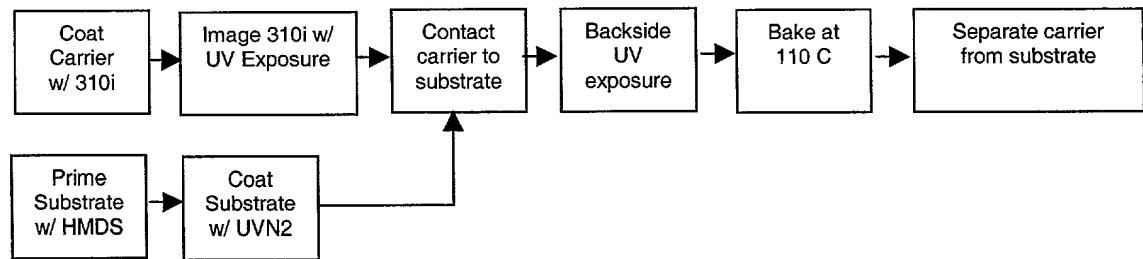


Figure 9a

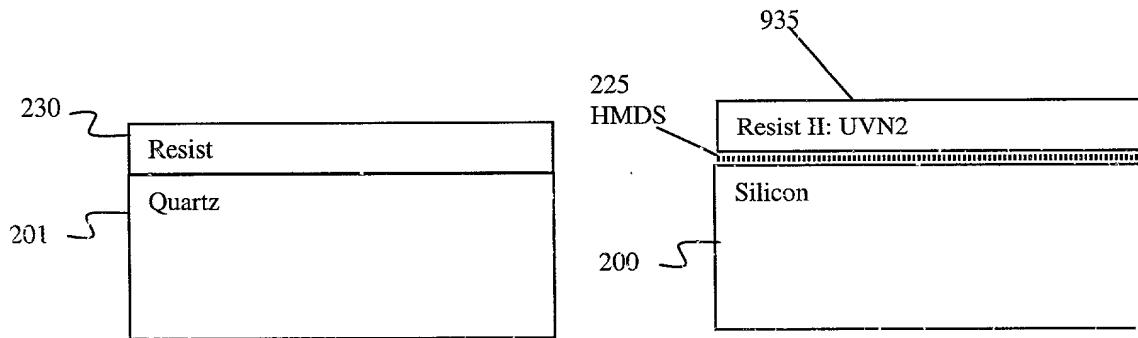


Figure 9b

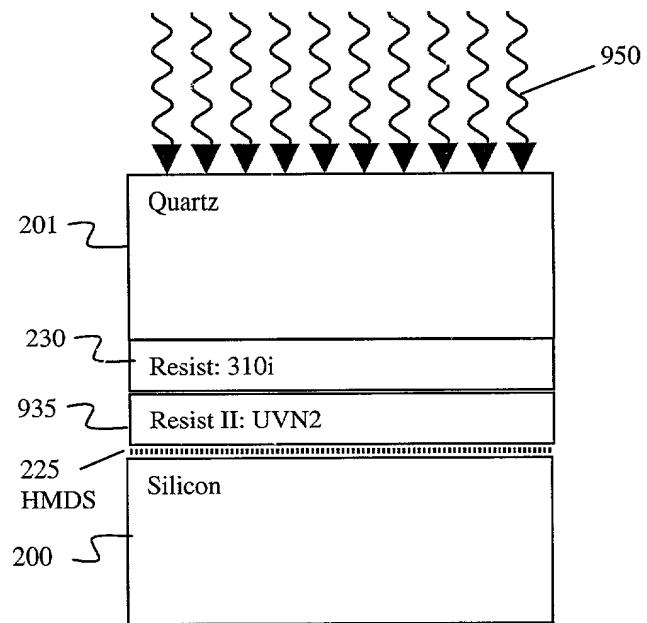


Figure 9c

DRAWINGS (Draft)

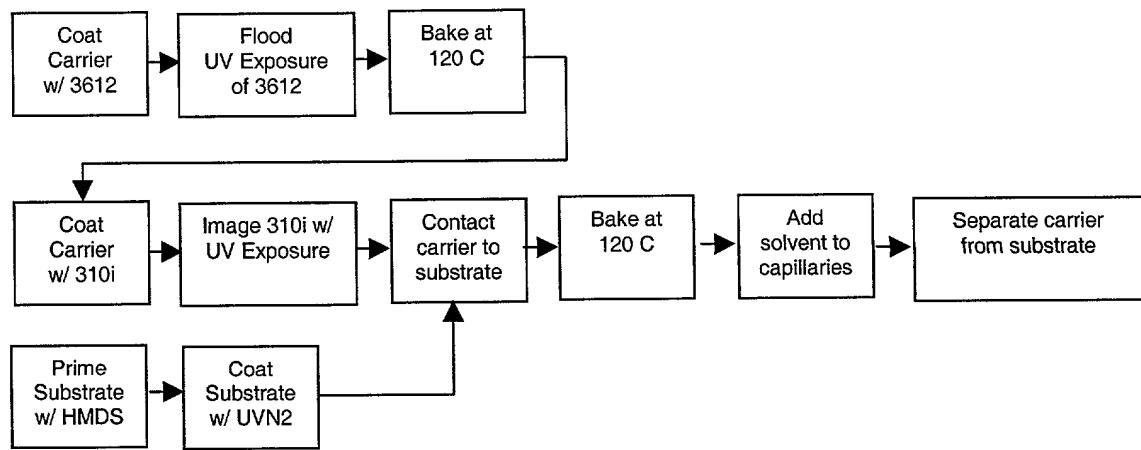


Figure 10a

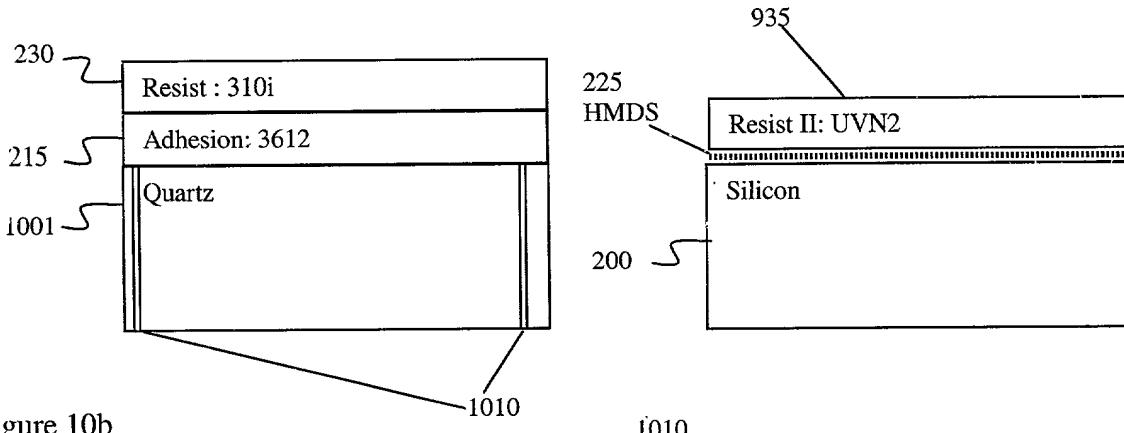


Figure 10b

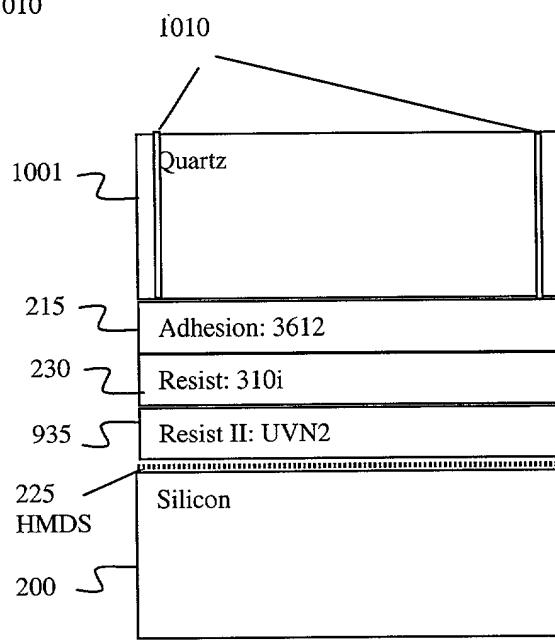


Figure 10c